

Quality of HiSIM_HV Model for Analog Circuit Design

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2-3 April 2009

a leap ahead
in Compact Modeling

Outline

Introduction (HiSIM_HV 1.0.2)

Model capabilities

Geometry Scalability

I-V results (I_d - V_g , I_d - V_d)

Self-heating Modelling

C-V results (Gate Oxide)

HiSIM_HV benchmark results

Comparison of benchmark circuit test

Summary

Table of Model Capabilities (1/3)

Physical Effects	HiSIM_HV 1.0.2
Technology:	
Quasi-Saturation	✓
RON	✓
Mobility	✓
Carrier Velocity Saturation	✓
Channel Length Modulation (CLM)	✓
Impact Ionization current (Substrate Current)	✓
Poly-Silicon-Gate Depletion Effects	✓
Geometry Scaling:	
SCE (Short Channel Effects)	✓
Reverse Short Channel Effects	✓
Narrow Channel Effects	✓
DIBL (Drain Induced Barrier Lowering)	✓

Table of Model Capabilities (2/3)

Physical Effects	HiSIM_HV 1.0.2
MOS Capacitance:	
Intrinsic Capacitance	☑
Overlap Capacitance	☑
Fringing Capacitance	☑
Bulk Diodes :	
Diode Current	☑ Only symmetrical
Diode Capacitance	☑ Only symmetrical
Temperature Modelling:	
Threshold Voltage	☑
Mobility	☑
Quasi-Saturation	☑
RON	☑
Impact Ionization (Bulk current)	☑
Self-heating	☑

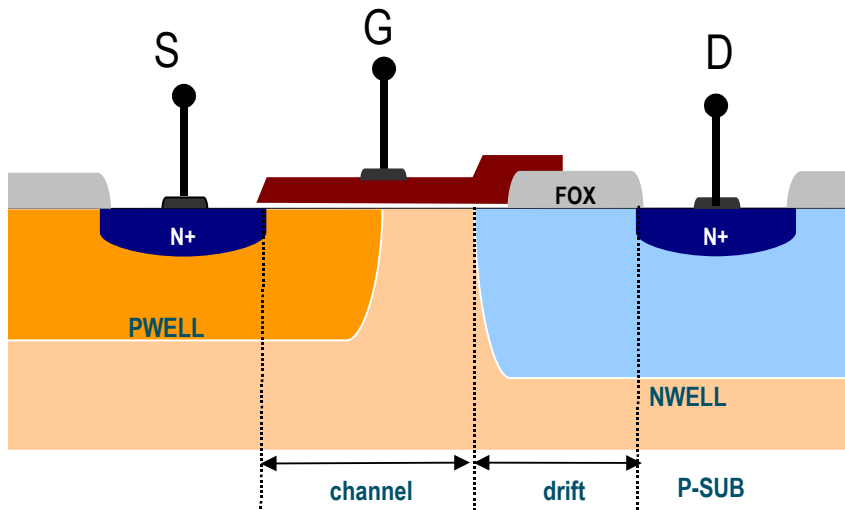
Table of Model Capabilities (3/3)

Physical Effects	HiSIM_HV 1.0.2
Noise:	
SPICE2 Noise model	☒
Flicker Noise Model	☑
Short-Channel Thermal Noise Model	☑
Induced Noise in Gate and Substrate	☑
RF:	
Gate resistance model	☑
Substrate resistance model	☑
Multi-finger transistors	☑
Non-Quasi-Static (NQS):	
NQS	☑

⇒ HiSIM_HV has been selected for CMC standardization

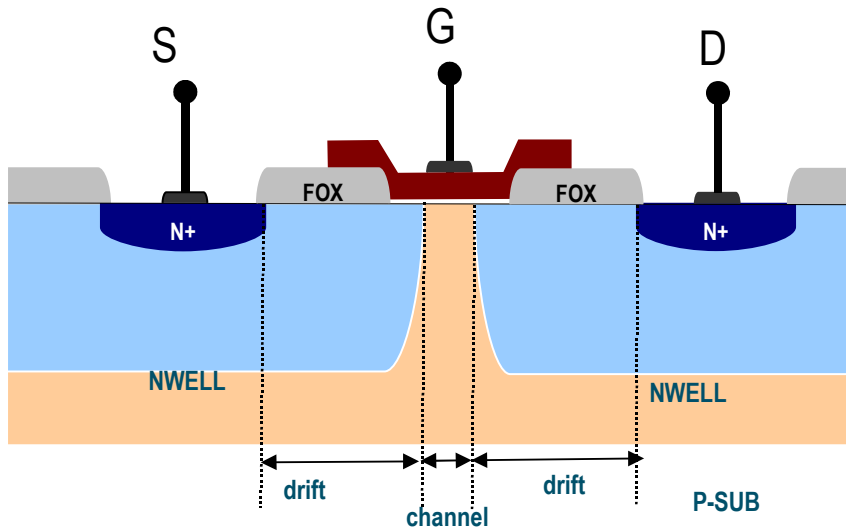
Cross-Section of LDMOS and HV-MOS

HiSIM_HV 1.0.2



Asymmetrical LDMOS

COSYM = 0

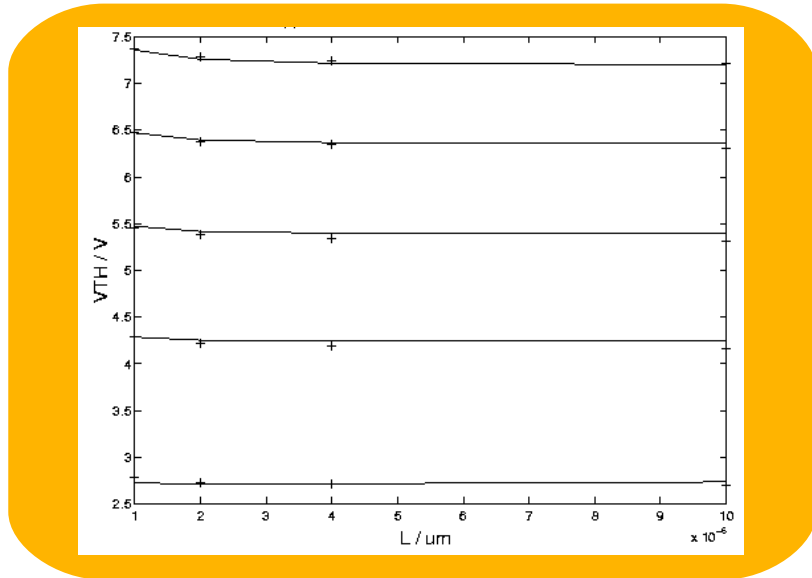


Symmetrical HV-MOS

COSYM = 1

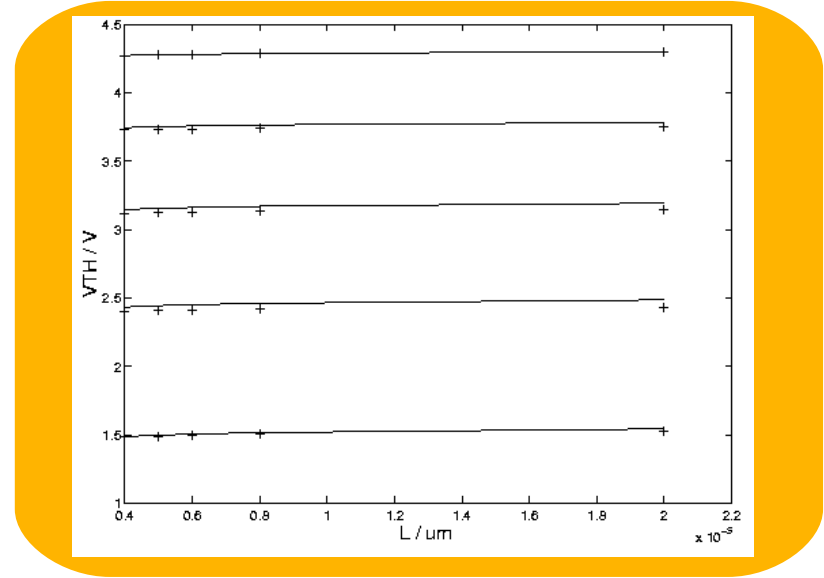
Geometry Scalable Modelling: Threshold Voltage

Asymmetrical NMOS



VTH vs. channel length

Symmetrical NMOS

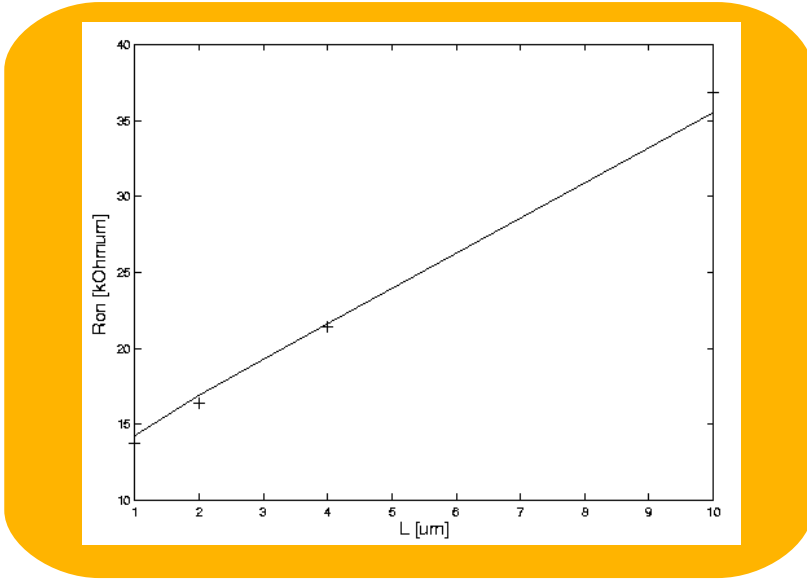


VTH vs. channel length

points: measurement; solid line: model

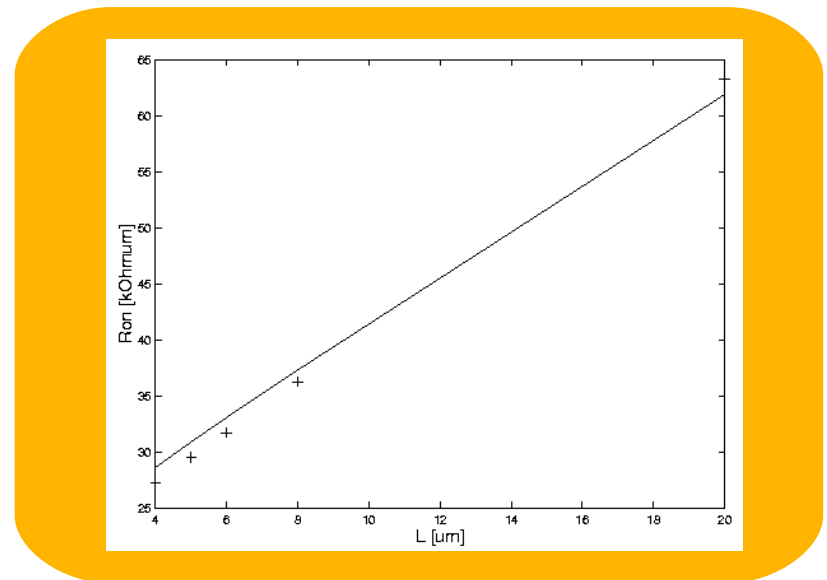
Geometry Scalable Modelling: on-resistance

Asymmetrical NMOS



On-resistance vs. channel length

Symmetrical NMOS

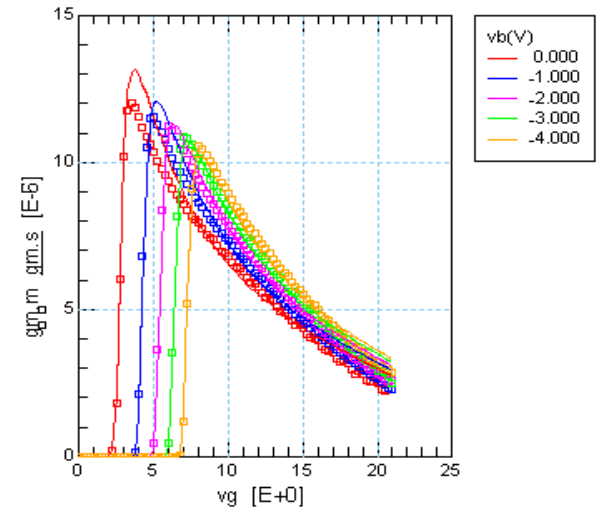
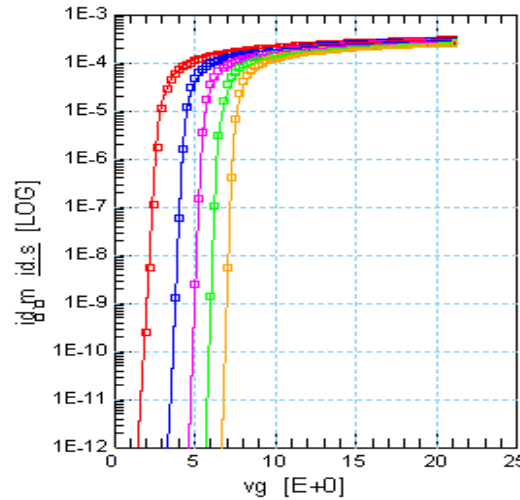
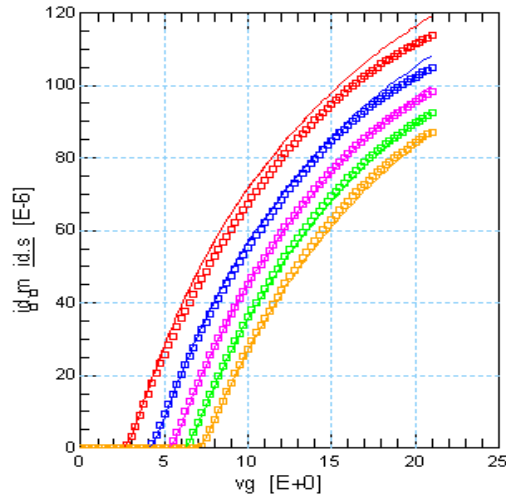


On-resistance vs. channel length

points: measurement; solid line: model

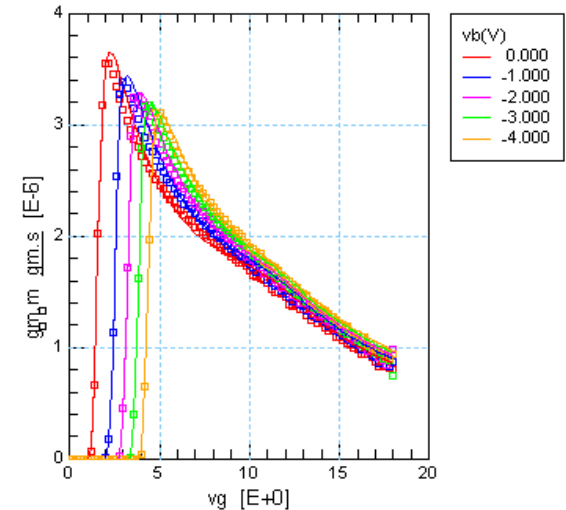
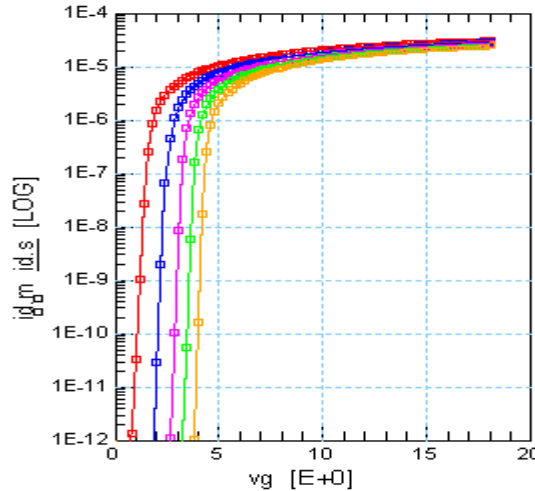
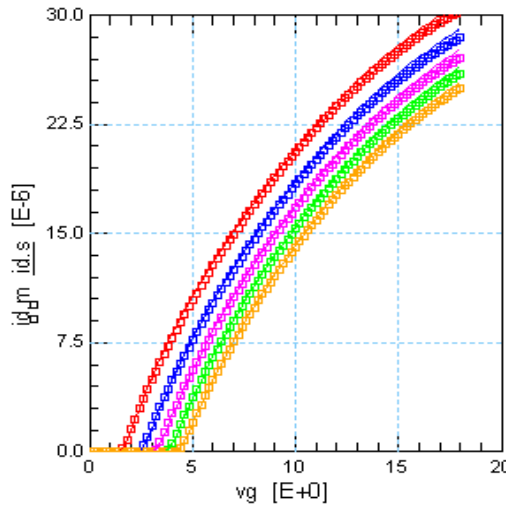
HiSIM_HV Modelling: Id-Vg Results (Large Device)

Asymmetrical NMOS



W/L: 40/10 μm ; points: measurement; solid line: model

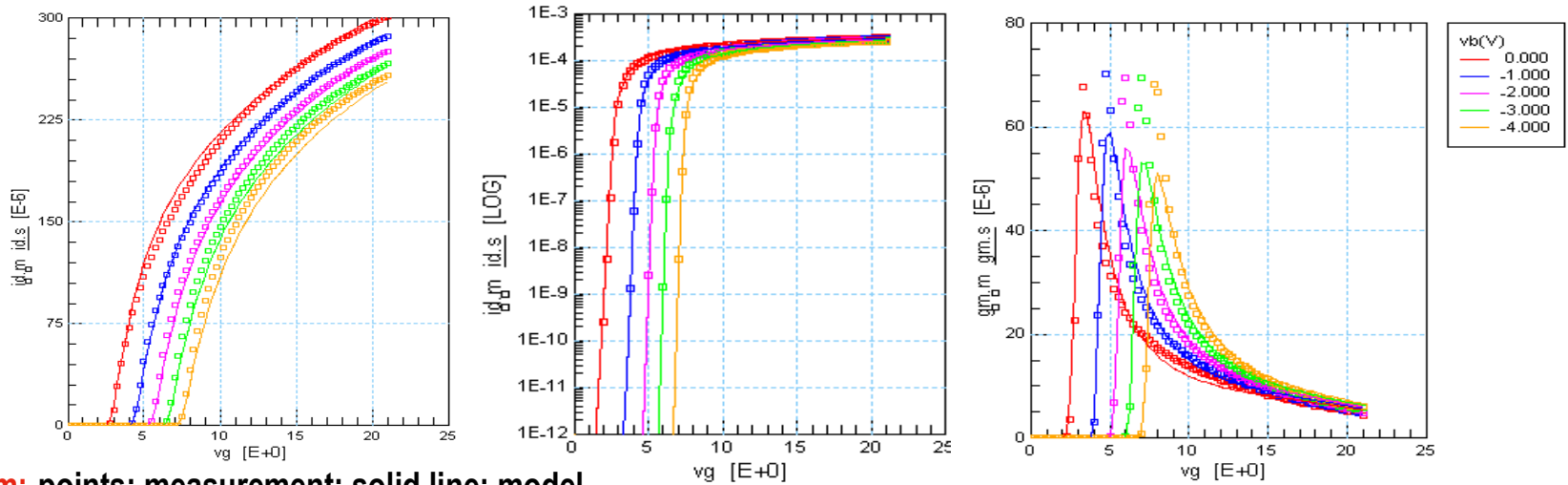
Symmetrical NMOS



W/L: 20/20 μm ; points: measurement; solid line: model

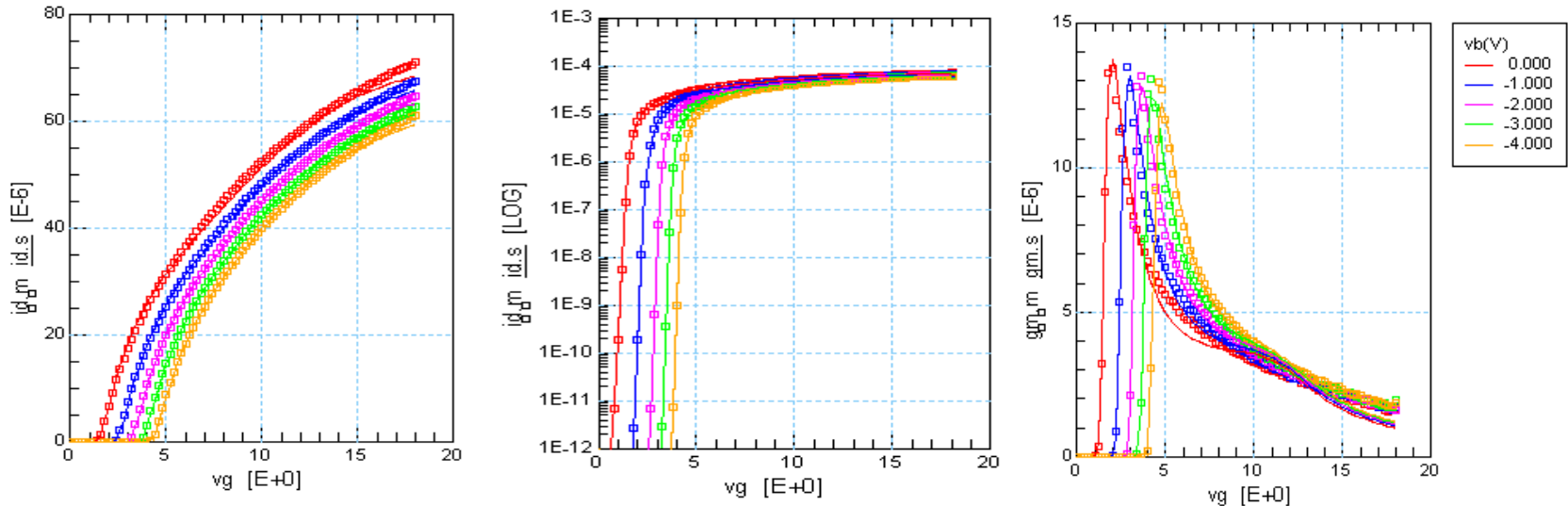
HiSIM_HV Modelling: Id-Vg Results (Short Device)

Asymmetrical NMOS



W/L: 40/1 um; points: measurement; solid line: model

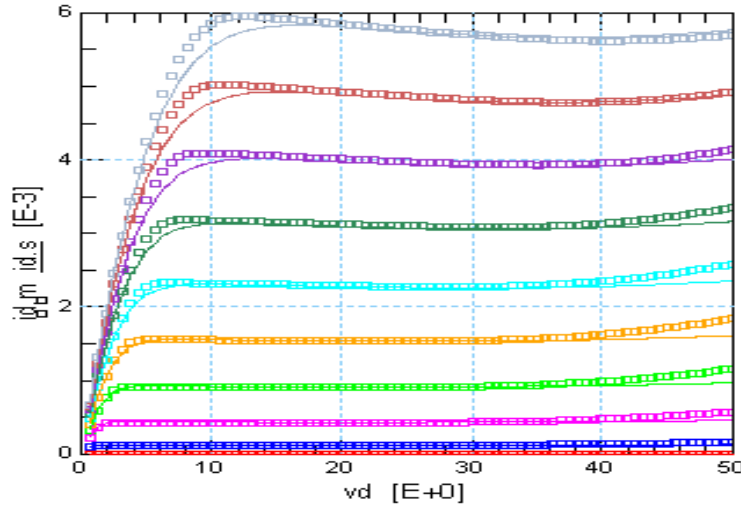
Symmetrical NMOS



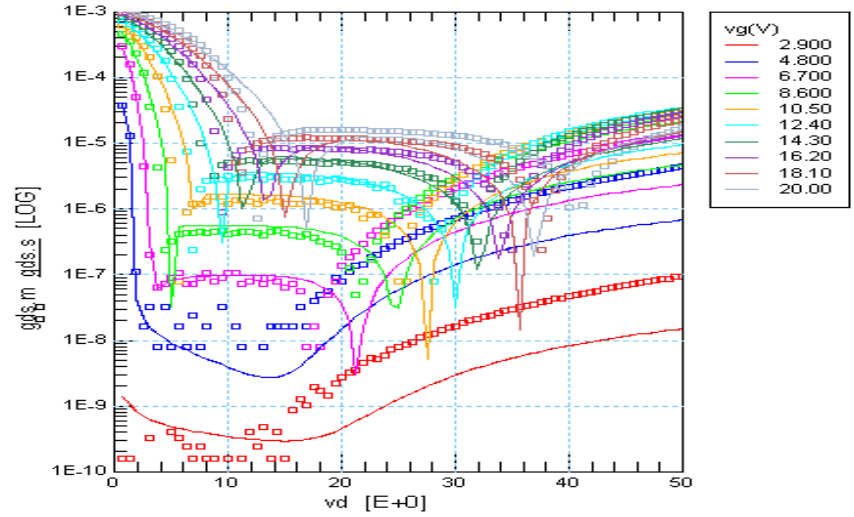
W/L: 20/4 um; points: measurement; solid line: model

HiSIM_HV Modelling: Id-Vd Results (Large Device)

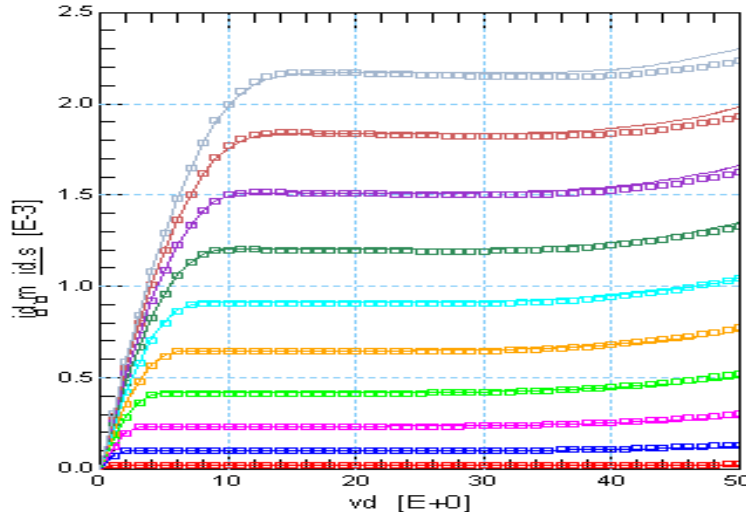
Asymmetrical NMOS



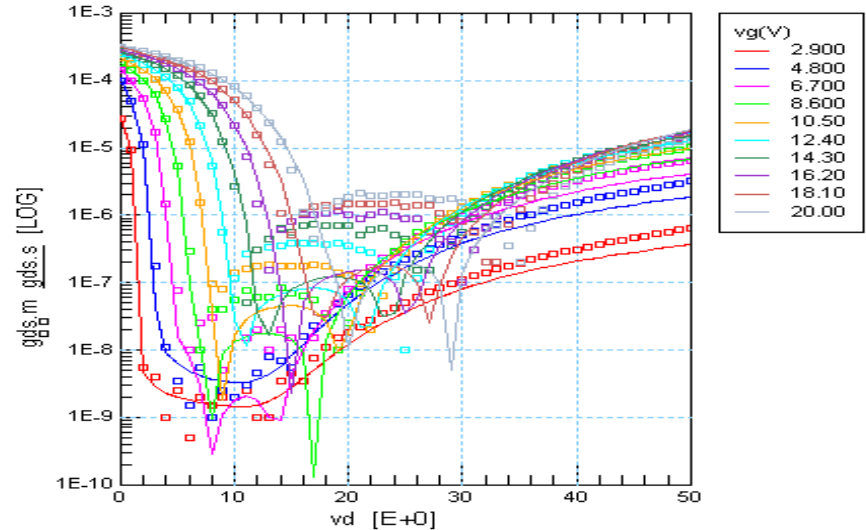
W/L: 40/10 μm ; points: measurement; solid line: model



Symmetrical NMOS

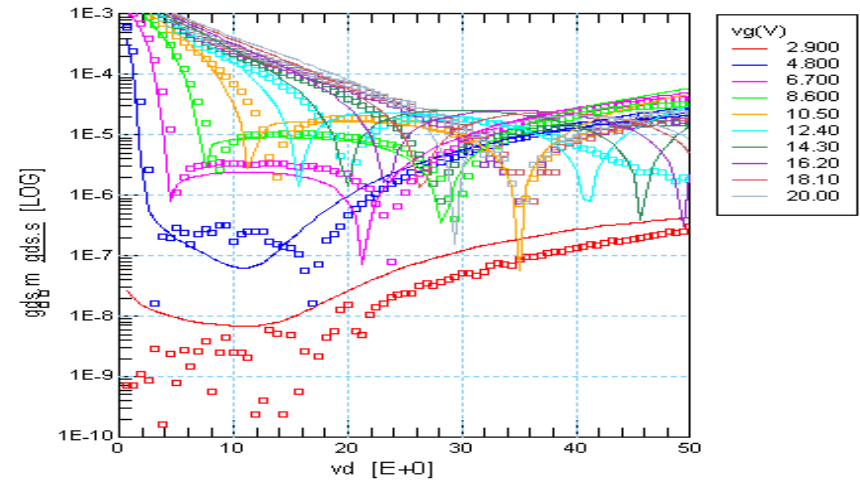
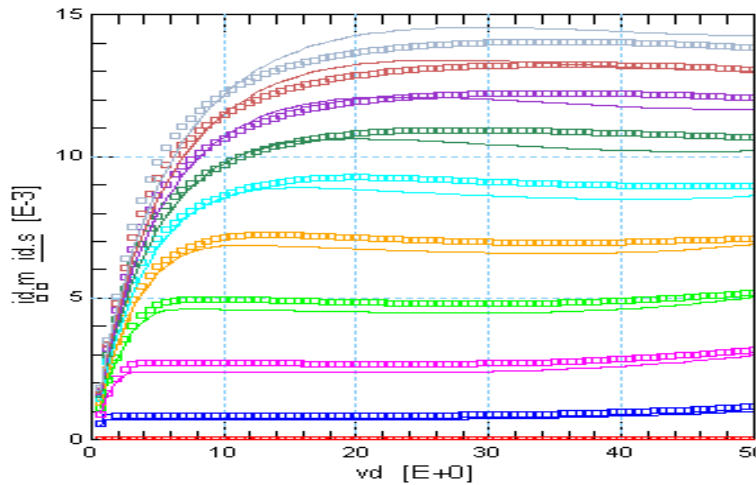


W/L: 20/20 μm ; points: measurement; solid line: model



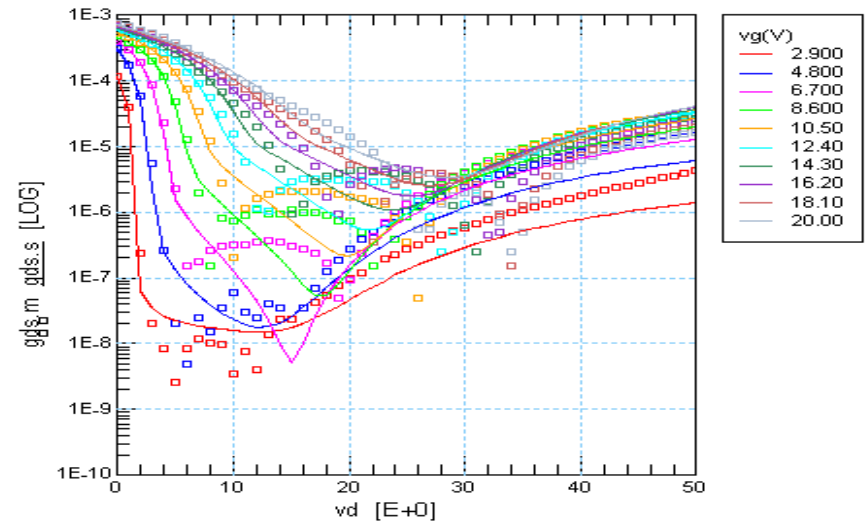
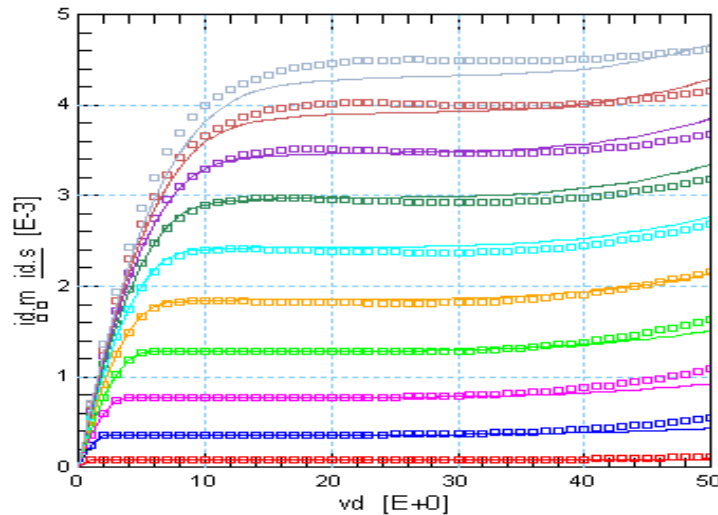
HiSIM_HV Modelling: Id-Vd Results (Short Device)

Asymmetrical NMOS



W/L: 40/1 μm ; points: measurement; solid line: model

Symmetrical NMOS



W/L: 20/4 μm ; points: measurement; solid line: model

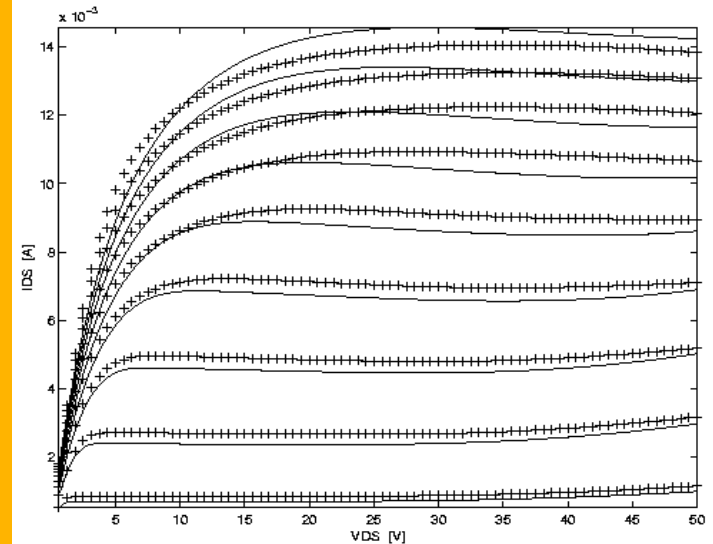
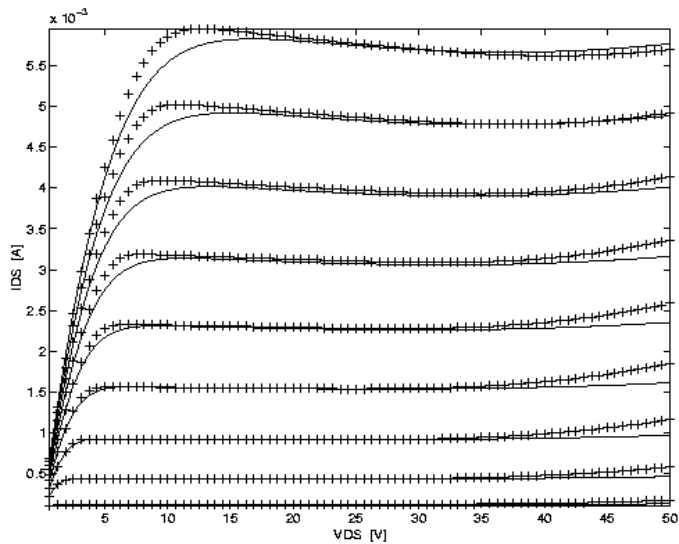
Self-Heating Modelling (Asymmetry NMOS)

W/L=40/10 um; Vgs=6.7(1.9) 20V

Self-heating modelling flag on

W/L=40/1 um; Vgs=2.9(1.9) 20V

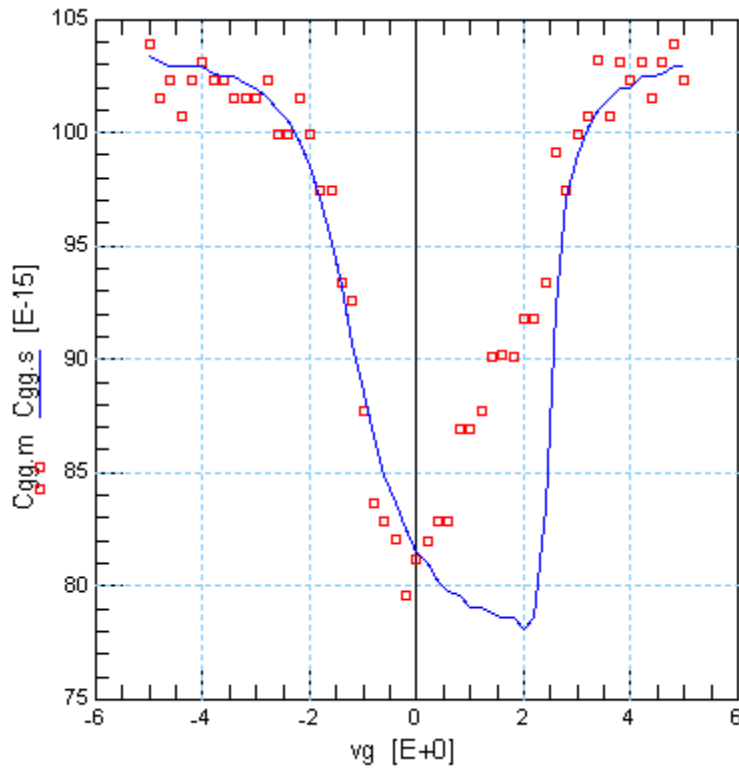
Self-heating modelling flag on



points: DC measurement with self-heating solid line: model

HiSIM_HV Modelling: C-V Results

Asymmetrical NMOS

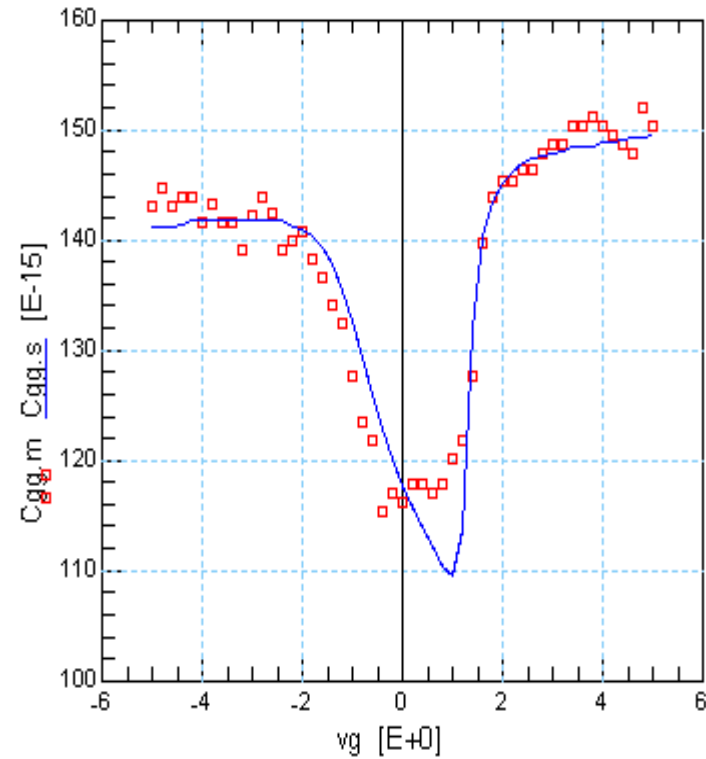


W/L= 40/1 um; Vds=0V

$$C_{gg} = \text{imag}(y_{11}) / \omega$$

points: measurement; solid line: model

Symmetrical NMOS

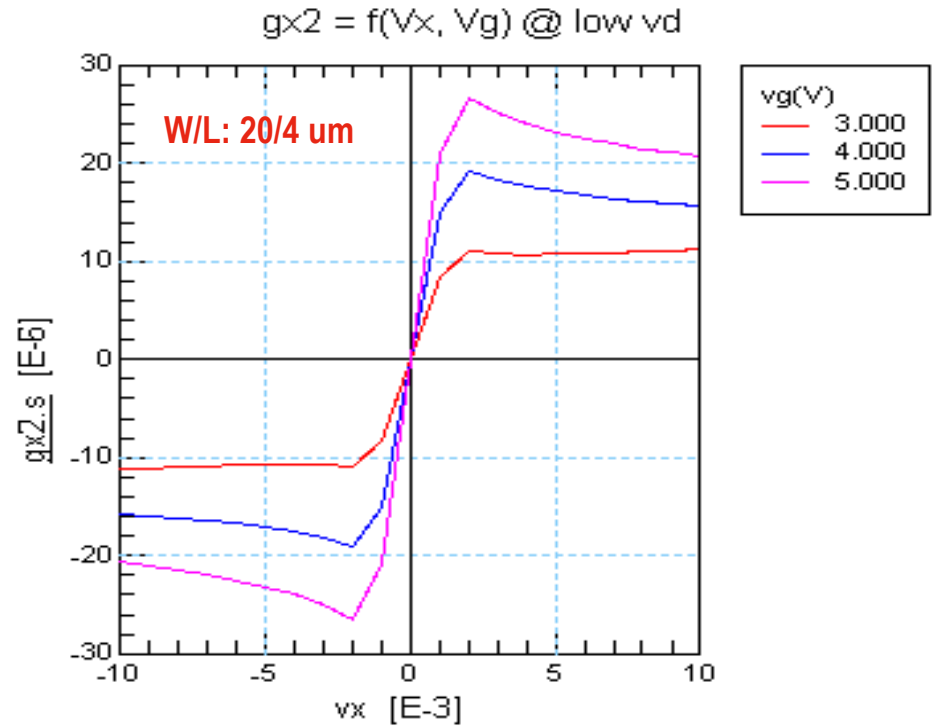
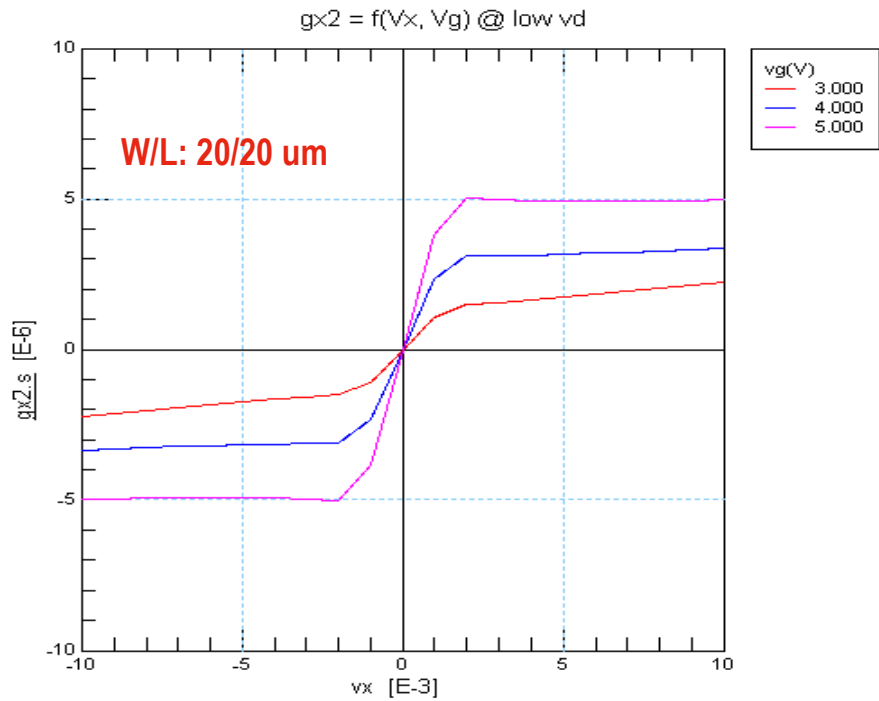


W/L= 20/4 um; Vds=0V

Benchmark Test

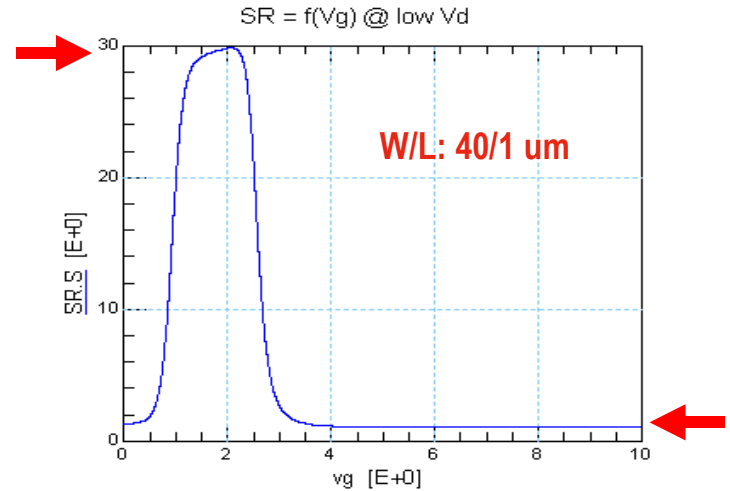
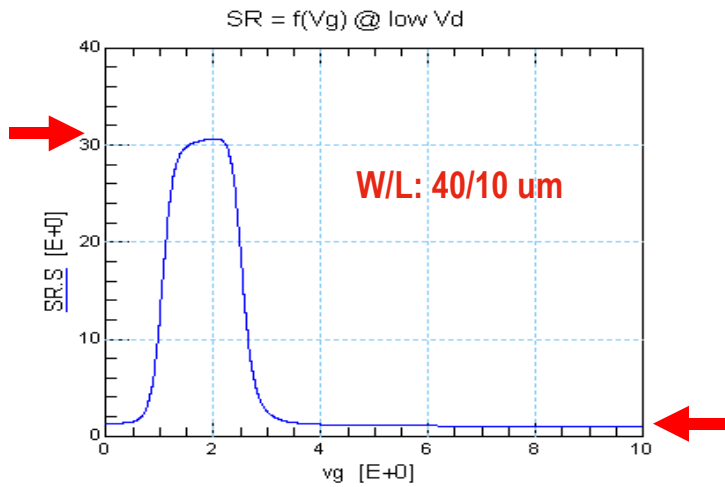
HiSIM_HV 1.0.2

HiSIM_HV 1.0.2: Gummel Symmetry Test (Symmetry NMOS)



HiSIM_HV 1.0.2: Gummel Slope Ratio Test

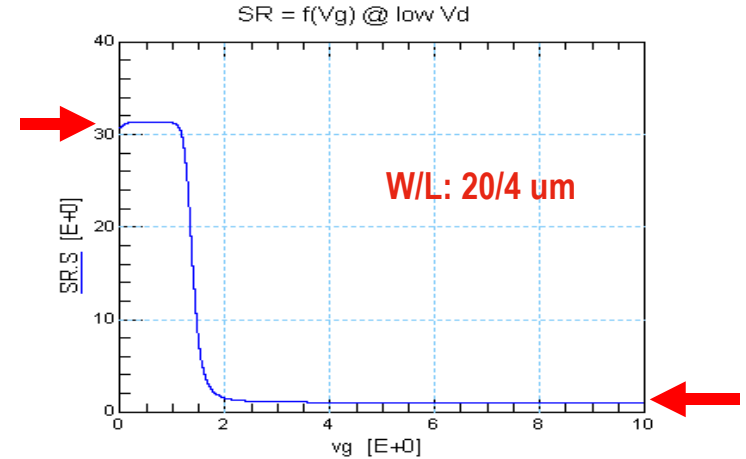
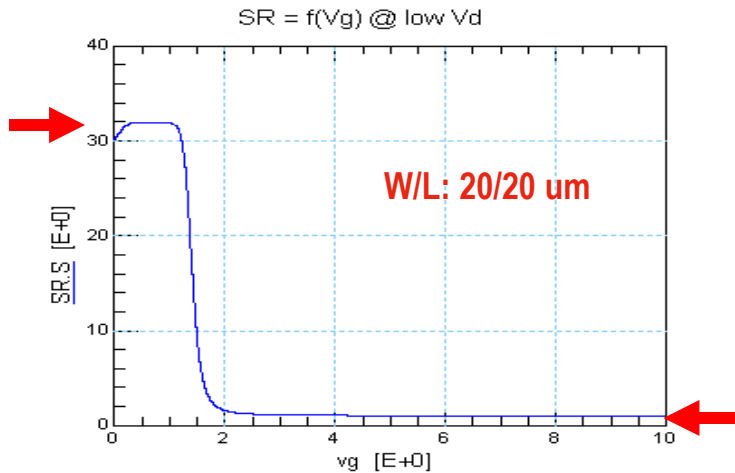
Asymmetrical NMOS



$$SR = \frac{(Id2 + Id1) * (Vd2 - Vd1)}{(Id2 - Id1) * (Vd2 + Vd1)}$$

Vd=0.1,0.2V; Vb=0V

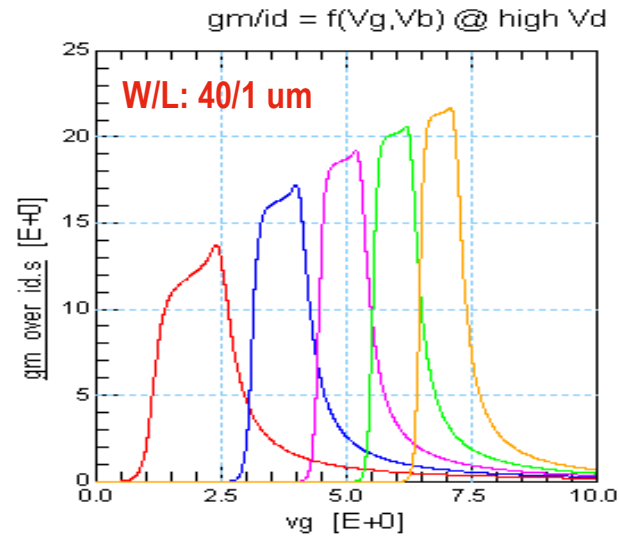
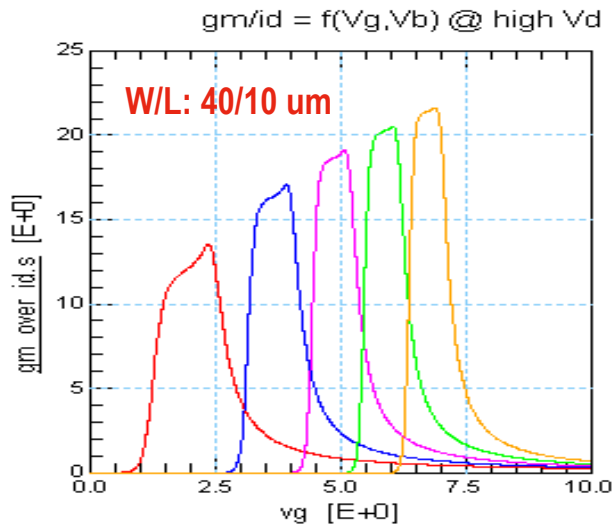
Symmetrical NMOS



Vd=0.1,0.2V; Vb=0V

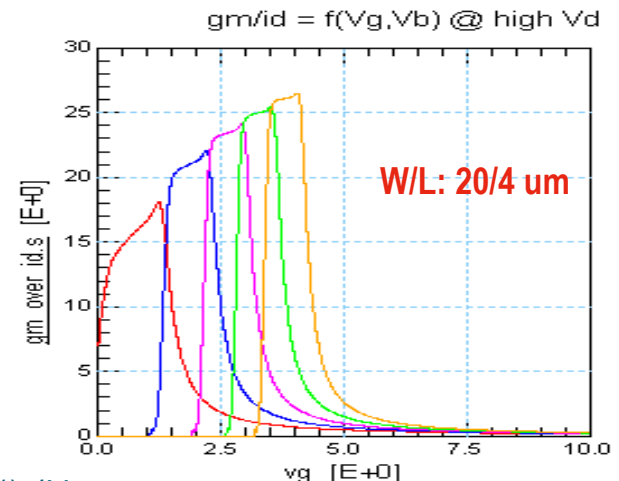
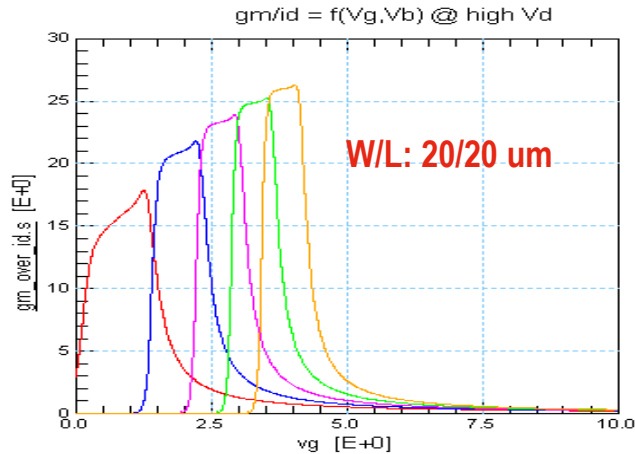
HiSIM_HV 1.0.2: Gummel Treetop Test

Asymmetrical NMOS



Vd=50V, Vb=0(-1)-4V

Symmetrical NMOS

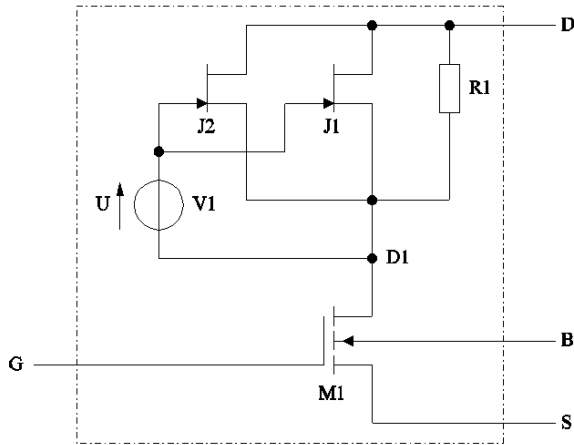


Vd=50V, Vb=0(-1)-4V

Benchmark Circuit Test Comparison: BSIM3-Sub-Circuit and HiSIM_HV 1.0.2

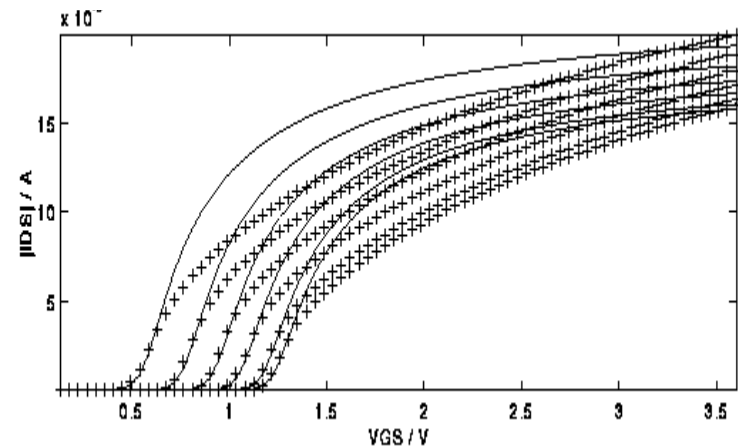
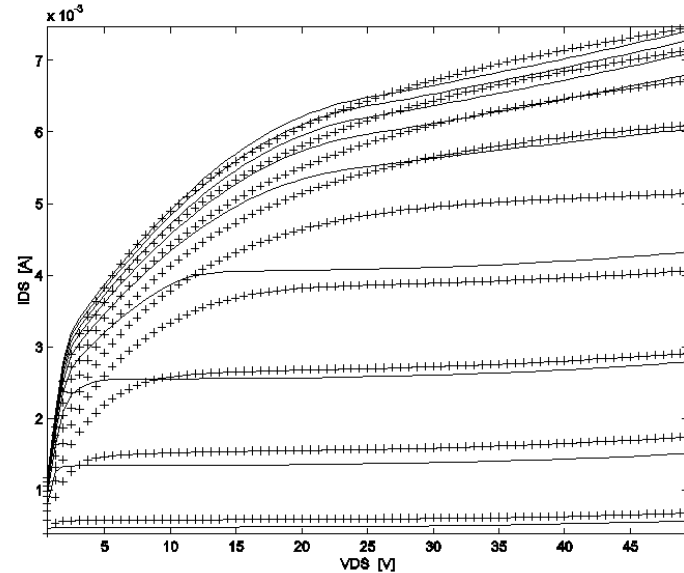
AMS BSIM3-Sub-Circuit Model for LDMOS and HV_MOS

BSIM3 based scalable sub-circuit model



Fitting problems:

- linear region
- quasi-saturation region



Benchmark Circuit I - Ringoscillator

Inverter chain:

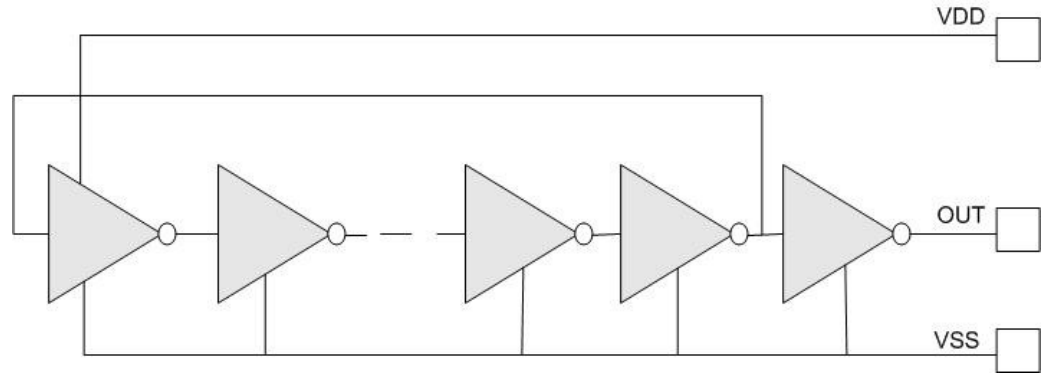
41 stages + 1 Buffer

Important parameters:

Rise time, fall time, periodity

Relevant SPICE parameters:

G-D capacitance models



Operating System:

Linux 32Bit,

Dual Core Intel CPU T2400 @ 1.83GHz

Simulation time comparison:

Transient simulation: 100ns

Total simulation Time:

Used Memory

Sub-circuit: 48,14s

9.56MB

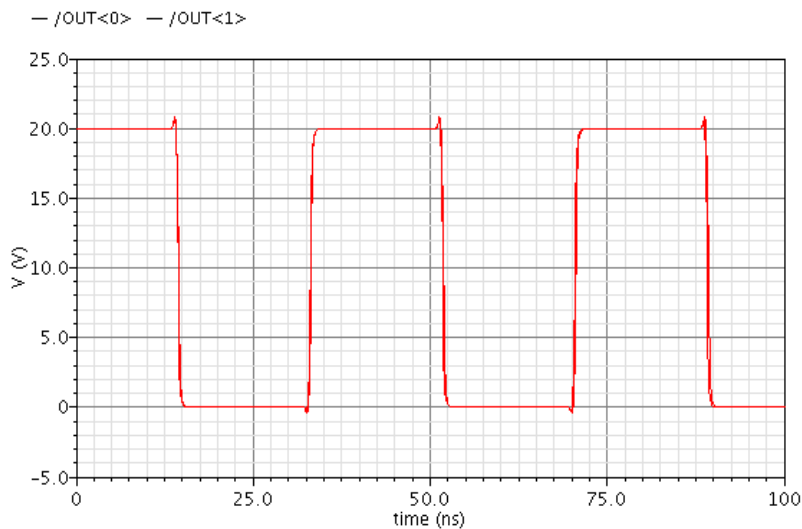
HISIM model: 34,45s

6.48MB

Delta [%]: ~30

~33

Transient Response



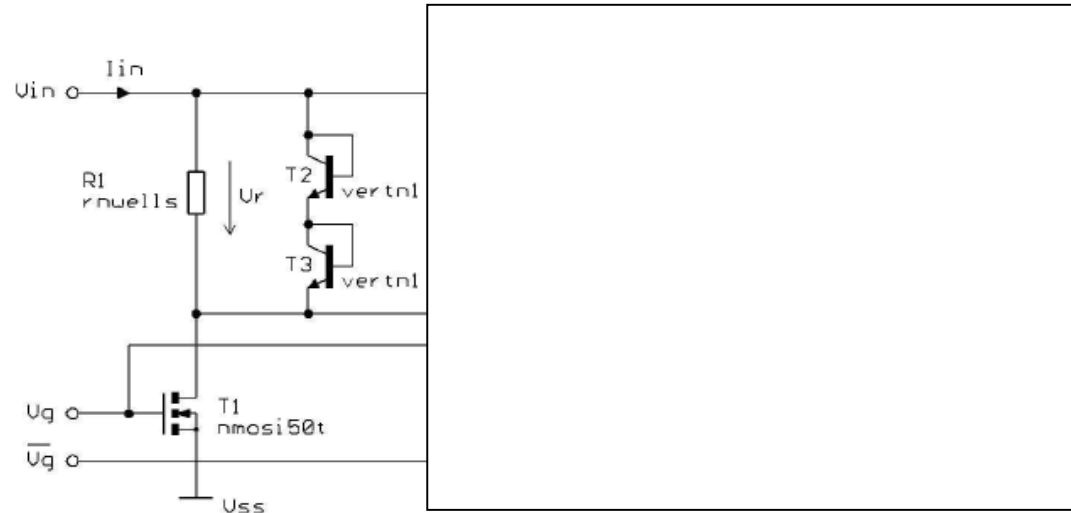
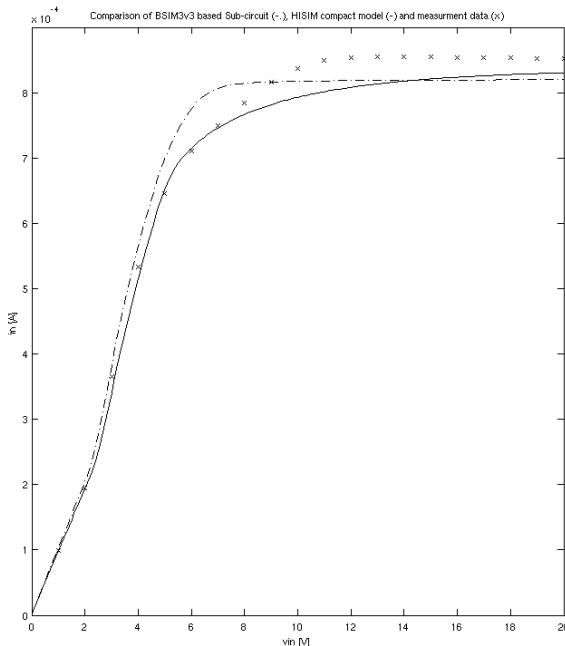
Benchmark Circuit II – Gate Switch

Operation:

Temperature stabilized Gate switch

Problem Specification:

Sub-circuit models differ because of too simple drain resistance model.



Accuracy check:

op:

$v_g=3.3V$,

v_{in} ramped over whole operating range

The linear region is expressed highly accurate by the compact model.

Smoother behavior of the whole curve.

Summary

- HiSIM_HV is a fully scalable analytical surface potential based model for HV MOSFETs, includes most of the physical effect due to drift region.
- Model results shows very good agreement with measurement data for both symmetrical and asymmetrical MOSFET devices
- Self-heating model is also verified and shows good accuracy
- Circuit benchmark test shows high speed of simulation and accuracy
- Model can be used for sufficient accuracy for low-risk design of high-voltage ICs.

Acknowledgment: We would like to thank W. Pfanzl and W. Posch for pulse measurement and HiSIM code implementation in MATLAB, respectively.

Thank you

